ELIONIX

Company Description

Since its foundation in 1975, Elionix has always aimed to create equipment that contributes to the advancement of cutting-edge science and technology and has introduced equipment for research and development of nanotechnology to the world.

In the field of electron beam lithography systems, in 1997 we developed an ultra-high-definition electron beam lithography system capable of writing lines 10 nm in width, which is 1/5 of the best specification of those days.

With the two CSs "Challenge and Speed" and "Customer Satisfaction" as our basic stance, we have always developed equipment ahead of our competitors, and we believe this is the reason why we have remained the top runner as a nanotechnology research equipment manufacturer.

Our R&D equipment has been introduced to universities and public institutions in Japan and around the world, and has received high acclaim.

We will continue to be your partner in solving your problems around the world, aiming to be a world brand company that provides the highest-performance equipment and the highest customer satisfaction.

Company Details

Head Office
Japan

Main Business
電子・イオン等の粒子線、および光・X線等の電磁波に関する技術を応用した各種機器・システムの研究・開発・設計・製造・販売・技術提供・輸出入・ 保守サービス等。

President
菊地　洋介

Established
1975年3月4日

Capital
2億7,000万円

Number of Employees
101 - 500

URL
http://www.elionix.co.jp

Offices

Main Office
3-7-6 Motokoya-machi, Hachioji-shi
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